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PATENT & TRADEMARK OFFICE

2823

PATENT

Atty. Dkt. No.AMAT/2966.X2/DSM/BCVD/JW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:
Rathi, et al

Serial No.: 09/165,248

Confirmation No.: 7619

Filed: October 1, 1998

For: A Silicon Carbide Deposition for Use as a Barrier Layer

Group Art Unit: 2823

Examiner: George R. Fourson, III

#32/Arnett H
Abram
5/20/03

CERTIFICATE OF MAILING
37 CFR 1.8
I hereby certify that this correspondence is being deposited on 4/28/03 with the United States Postal Service as First Class Mail in an envelope addressed to: Commissioner for Patents, Washington, D.C. 20231.

4/28/03
Date

Signature

Commissioner for Patents
Washington, D.C. 20231

Dear Sir:

RESPONSE TO OFFICE ACTION DATED JANUARY 28, 2003

In response to the Office Action dated January 28, 2003, having a shortened statutory period for response set to expire on April 28, 2003, please enter this response and reconsider the claims pending in the application for reasons discussed below. Although Applicant believes that no fee is due in conjunction with this response, the Commissioner is hereby authorized to charge counsel's Deposit Account No. 20-0782/AMAT/2966.X2/KMT, for any fees, including extension of time fees or excess claim fees, required to make this response timely and acceptable to the Office.

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IN THE CLAIMS:

Please amend the claims as follows:

15. (Fourth Amendment) A method for processing a substrate, comprising: